

Abstract

AQUEOUS DISPERSION, PROCESS FOR ITS PRODUCTION AND USE

Aqueous dispersion containing a silicon-aluminum mixed
oxide powder, the powder containing 0.1 to 99.9 wt.% Al_2O_3 and
5 Si-O-Al-bonds. The dispersion can be produced using dispersing
and/or grinding devices which achieve an energy input of at
least 200 KJ/m³. The dispersion can be used for the chemical-
mechanical polishing of semiconductor substrates.